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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/455,991	12/06/1999	HISASHI OHTANI	07977/213002	5835
26171 75	590 03/21/2005		EXAM	INER
FISH & RICHARDSON P.C.			DIAZ, JOSE R	
1425 K STREET, N.W. 11TH FLOOR			ART UNIT	PAPER NUMBER
WASHINGTON, DC 20005-3500		_	2815	
			DATE MAIL ED. 02/21/200	e

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	09/455,991	OHTANI ET AL.				
Office Action Summary	Examiner	Art Unit				
	José R. Díaz	2815				
The MAILING DATE of this communication a Period for Reply	appears on the cover sheet with the	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REF THE MAILING DATE OF THIS COMMUNICATION  - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a real of the period for reply is specified above, the maximum statutory perions are to reply within the set or extended period for reply will, by state any reply received by the Office later than three months after the material patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a reply be tile reply within the statutory minimum of thirty (30) day od will apply and will expire SIX (6) MONTHS from tute, cause the application to become ABANDONE	mely filed  ys will be considered timely.  the mailing date of this communication.  ED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 04	January 2005.	•				
2a) ☐ This action is FINAL. 2b) ☐ T	his action is non-final.					
3) Since this application is in condition for allow closed in accordance with the practice unde						
Disposition of Claims						
4)	rawn from consideration. are rejected.					
Application Papers						
9)☐ The specification is objected to by the Exami	iner.					
10) ☐ The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.						
Applicant may not request that any objection to the		• 1				
Replacement drawing sheet(s) including the corr 11) The oath or declaration is objected to by the						
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreignation and All b) Some * c) None of:  1. Certified copies of the priority documents of the priority documents.  2. Certified copies of the priority documents.  3. Copies of the certified copies of the priority documents.  * See the attached detailed Office action for a life.	ents have been received. ents have been received in Applicat riority documents have been receiv eau (PCT Rule 17.2(a)).	ion No ed in this National Stage				
Attachment(s)						
Notice of References Cited (PTO-892)  Notice of Draftsperson's Patent Drawing Review (PTO-948)  Information Disclosure Statement(s) (PTO-1449 or PTO/SB/C Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail D  5) Notice of Informal 6 6) Other:					

Art Unit: 2815

### **DETAILED ACTION**

## Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless - .

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 6-12, 14-16, 18, 20-21 and 23-79 are rejected under 35 U.S.C. 102(e) as being anticipated by Zhang (US Pat. No. 5,922,125).

The applied reference has a common assignee with the instant application. Based upon the earlier effective U.S. filing date of the reference, it constitutes prior art under 35 U.S.C. 102(e). This rejection under 35 U.S.C. 102(e) might be overcome either by a showing under 37 CFR 1.132 that any invention disclosed but not claimed in the reference was derived from the inventor of this application and is thus not the invention "by another," or by an appropriate showing under 37 CFR 1.131.

Regarding claims 6, 9, 24, 31, 40, 48, 55 and 64, Zhang teaches a method of manufacturing a semiconductor device, said method comprising:

forming an amorphous semiconductor film (103) on an insulating surface (11, 12) (see fig. 1B);

Art Unit: 2815

providing a metal element (101, 102, 108, 109, and 110) being capable of promoting crystallization of the amorphous semiconductor film to form a first metal element added region (101 and 102) and a second metal element added region (108 and 110);

crystallizing the amorphous semiconductor film (103) from the first metal element added region (101 and 102) and the second metal element added region (108 and 110) in parallel to the substrate (104, 105, 106, 107) to form a first crystalline portion and a second crystalline portion, respectively, in a crystalline semiconductor film (see fig. 1A and 1B, and abstract); and

patterning the crystalline semiconductor film to form at least one crystalline semiconductor island of a functional array of semiconductor islands (201) (see fig. 2), using the first crystalline portion (consider the portion the include the islands 201) while the second crystalline portion (consider the portions formed between the islands 201 and the metal element added regions 101, 102, 108, 109,110) that is not used to form any crystalline semiconductor island of the functional array of semiconductor islands (see fig. 2),

wherein the second crystalline portion is located between the crystalline semiconductor island and the second metal element added region (consider the portions located between islands 201 and the metal element added regions 108 and 110 in fig. 2),

Art Unit: 2815

wherein the first metal element added region is away from the second metal element added region (please note that regions 101 and 102 are spaced apart from regions 108 and 110. See Fig. 2).

In addition, Zhang further teaches:

- With regards to claims 9 and 40, the limitation that the second metal element added region (108 and 110) is located at a peripheral edge of the group of active elements (201) (see fig. 2).
- With regards to claims 24 and 48, the limitation that the second crystalline portion extends along an entire length of the second metal element added region (consider the portions located between islands 201 and regions 108 and 110 in fig. 2).
- With regard to claims 55 and 64, the limitation that the crystalline island constitutes a TFT (see col. 5, lines 53-56).

Regarding claims 7, 32, 56 and 72-79, Zhang teaches that the metal added regions has a length extending 100 μm or more (see col. 6, lines 61-67).

Regarding claims 8, 10, 25, 33, 41, 49, 57, and 65, Zhang teaches that the metal element comprises Ni (see col. 3, lines 14-16).

Regarding claims 11-12, 26-27, 34-35, 42-43, 50-51, 58-59, and 66-67, Zhang teaches that the metal element is provided by ion implantation or by coating a solvent comprising the metal element (see col. 7, lines 19-24).

Regarding claims 14, 18, 28, 36, 44, 52, 60, and 68, Zhang teaches that the amorphous semiconductor film (103) comprises silicon (see col. 5, lines 64-65).

Art Unit: 2815

Regarding claims 15-16, 20-21, 29-30, 37-38, 45-46, 53-54, 61-62, 69-70, Zhang teaches that the semiconductor device includes at least one selected from the group consisting of an n-channel TFT and a p-channel TFT (see col. 3, lines 19-25 and col. 9, lines 1-3), wherein the n-channel thin film transistor has a first S value not lower than 75 mV/dec while the p-channel TFT has a second S value not lower than 75 mV/dec (see col. 13, lines 53-54).

Regarding claims 23, 39, 47, 63, and 71, Zhang teaches that the crystal growth state is controlled by the second metal element added region (108 and 110) (see figs. 1A and 2).

## Response to Arguments

3. Applicant's arguments filed January 4, 2005 have been fully considered but they are not persuasive. The arguments are not persuasive since Zhang explicitly teaches the new limitation of growing crystals in directions parallel to the substrate (see abstract, and arrows (104) to (107) in figure 1B).

#### Conclusion

4. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not

Art Unit: 2815

Page 6

mailed until after the end of the THREE-MONTH shortened statutory period, then the

shortened statutory period will expire on the date the advisory action is mailed, and any

extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

the advisory action. In no event, however, will the statutory period for reply expire later

than SIX MONTHS from the mailing date of this final action.

Correspondence

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to José R. Díaz whose telephone number is (571) 272-

1727. The examiner can normally be reached on Monday through Thursday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Tom Thomas can be reached on (571) 272-1664. The fax phone number

for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the

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TOM THOMAS SUPERVISORY PATENT EXAMINER

JRD

3/16/05